## Claims

- [c1] A metrology process for increasing image contrast of a buried feature, comprising:

  milling a selected surface of a substrate to expose a cross section of the buried feature;

  exposing the exposed cross section with a gas mixture,

  wherein the gas mixture comprises a fluorine bearing compound; and

  irradiating the exposed cross section with a high energy beam to increase image contrast of the buried feature.
- [c2] The metrology process of Claim 1, wherein the high energy beam comprises an ion beam, and electron beam, a plasma, or a laser.
- [c3] The metrology process of Claim 1, wherein milling forms a wall substantially perpendicular to a major plane of the substrate.
- [c4] The metrology process of Claim 1, further comprising recording an image of the exposed cross section at an angle from the substantially perpendicular wall.
- [c5] The metrology process of Claim 4, wherein recording the image comprises scanning electron microscopy.
- [c6] The metrology process of Claim 1, wherein the milling comprises exposing the selected surface to a focused ion

APP\_ID=10604110 Page 15 of 22

beam.

- [c7] The metrology process of Claim 1, the milling comprises exposing the selected surface to a focused ion beam and a noble gas halide selected from the group consisting of XeF<sub>2</sub>, XeF<sub>4</sub>, XeF<sub>6</sub>, KrF<sub>2</sub>, KrF<sub>4</sub>, and KrF<sub>6</sub>.
- [c8] The metrology process of Claim 4, further comprising filling the exposed cross section subsequent to recording the image.
- [c9] The metrology process of Claim 1, wherein milling and exposing the exposed cross section occurs in a dual beam exposure apparatus.
- [c10] The metrology process of Claim 1, wherein the fluorine bearing compound comprises a formula of  $C_xH_yF_z$ , wherein x ranges from 1 to 4, y ranges from 0 to 9 and z ranges from 1 to 10.
- [c11] The metrology process of Claim 1, wherein the fluorine bearing compound comprises CF<sub>4</sub>, HF, NF<sub>3</sub>, F<sub>2</sub>, SF<sub>6</sub> or a combination comprising at least one of the foregoing fluorine bearing compounds.
- [c12] The metrology process of Claim 1, wherein the fluorine bearing compound is less than about 80 parts by volume of the second gas mixture.
- [c13] The metrology process of Claim 1, wherein the gas mixture

APP\_ID=10604110 Page 16 of 22

comprises the fluorine bearing compound and an oxidizing gas.

- [c14] The metrology process of Claim 13, wherein the oxidizing gas comprises O<sub>2</sub>, NO, water vapor, or mixtures comprising at least one of the foregoing oxidizing gases.
- [c15] A metrology process for enhancing an image contrast between an oxide layer in contact with a nitride layer; comprising: exposing a cross section comprising the oxide layer in contact with the nitride layer with a gas mixture, wherein the gas mixture comprises a fluorine bearing compound; and irradiating the exposed cross section with an ion beam or an electron beam or a plasma beam or a laser to increase the image contrast between the oxide layer and the nitride layer.
- [c16] The metrology process of Claim 15, wherein the fluorine bearing compound comprises a formula of C<sub>x</sub>H<sub>y</sub>F<sub>z</sub>, wherein x ranges from 1 to 4, y ranges from 0 to 9 and z ranges from 1 to 10.
- [c17] The metrology process of Claim 15, wherein the fluorine bearing compound comprises CF<sub>4</sub>, HF, NF<sub>3</sub>, F<sub>2</sub>, SF<sub>6</sub> or a combination comprising at least one of the foregoing fluorine bearing compounds.
- [c18] The metrology process of Claim 15, wherein the fluorine bearing compound is less than about 80 parts by volume of

Page 17 of 22

APP ID=10604110

the gas mixture.

- [c19] The metrology process of Claim 15, wherein the gas mixture further comprises an oxidizing gas.
- [c20] The metrology process of Claim 19, wherein the oxidizing gas comprises O<sub>2</sub>, NO, water vapor, or mixtures comprising at least one of the foregoing oxidizing gases.